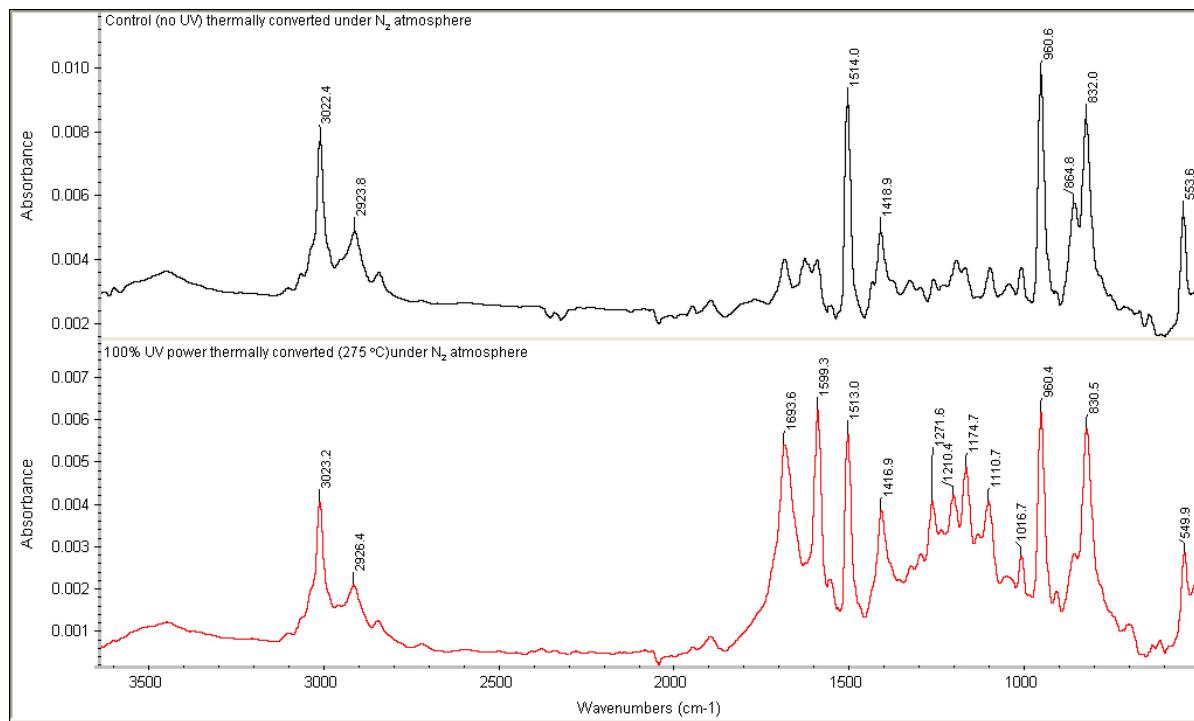


Supporting Information

UV-Vis spectroscopy was performed using a Perkin Elmer Lambda 950 UV/Vis spectrometer. The UV-light source used for UV dosage studies and photolithography was a Fusion UV system model I6B. A collimated deep UV (280 – 310 nm) light source (AMB, Inc. ST100) was also used for photolithography. Film thickness measurements were performed using a Dektak IIA profilometer or a KLA Tencore model P-15 profilometer.

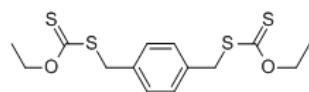
X-ray photoelectron spectroscopy (XPS) was performed with a Kratos Axis Ultra DLD with monochromatic Al Ka excitation (1486.6 eV). The analyzed spot size was 300x700 micrometers and chamber base pressures were less than 5×10^{-9} Torr. Survey spectra were taken with Pass Energy 80, 200 ms dwell times, and 1 eV steps. High resolution core level spectra were recorded with a pass energy 20 and 0.1 eV steps. Quantification and data fitting were performed with CasaXPS software.

FTIR was performed using a Thermo Nicolet 6700 spectrometer using Thermo KBr 25 x 4 mm discs. A solution of the polymer (2.5% w/w in dichloroethane) was spin-coated onto KBr discs (1,500 RPM). The samples were heated to 100 °C for 5 min, and one of the samples was run through the Fusion UV system at 100% power. The samples were thermally converted (275 °C) under a N₂ atmosphere and the FTIR spectra were recorded. FTIR spectra were consistent with (and based on) previous literature reports.^{1,2} Control: wavenumbers (cm⁻¹) 3022 (trans-vinylene CH stretch), 2924 (aliphatic CH stretch), 1514, 1419 ('semi-circle' ring stretch), 961 (trans-vinylene CH out-of-plane bend), 865 (cis-vinylene CH out-of-plane bend) 832 (*p*-phenylene CH out-of-plane bend), 554 (*p*-phenylene out-of-plane ring bend). 100% UV power: wavenumbers (cm⁻¹) 3023 (trans-vinylene CH stretch), 2926 (aliphatic CH stretch), 1694 (carbonyl stretch), 1599 (substituent perturbation of *p*-phenylene ring)², 1513, 1417 ('semi-circle' ring stretch), 1271, 1175, 1111 (*p*-phenylene CH in-plane bend), 1210 (vinylene CH in-plane bend) 960 (trans-vinylene CH out-of-plane bend), 830 (*p*-phenylene CH out-of-plane bend), 550 (*p*-phenylene out-of-plane ring bend).

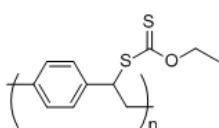


Synthesis of the ethylxanthate monomer and polymer were based off a previous literature report.³ All chemicals were purchased from Fisher Scientific and were used without further purification. ¹H and ¹³C NMR spectra were recorded on a Bruker model DRX400 or Bruker AVANCE 500 spectrometer. Proton and carbon chemical shifts are reported relative to the solvent, which was used as an internal standard. Anhydrous THF and t-BuOK (1.0 M in THF) were purchased in AcroSeal bottles. Precursor polymers were isolated using a Fisher Scientific centrifuge operating at 6,000 rpm. GPC analysis was performed on a Polymer Labs 220 PL-GPC equipped with two columns operated in series: a PLgel 5 μm MiniMIC-C (250mm x 4.6mm) and a PLgel 5 μm

MiniMIX-C (50mm x 4.6mm) guard column. Chloroform was used as the eluent (0.4 mL/min), and measurements were performed at 35 °C. Calibration was performed using polystyrene standards with narrow molecular weight distributions (Fluka ReadyCal 400-2,000,000).



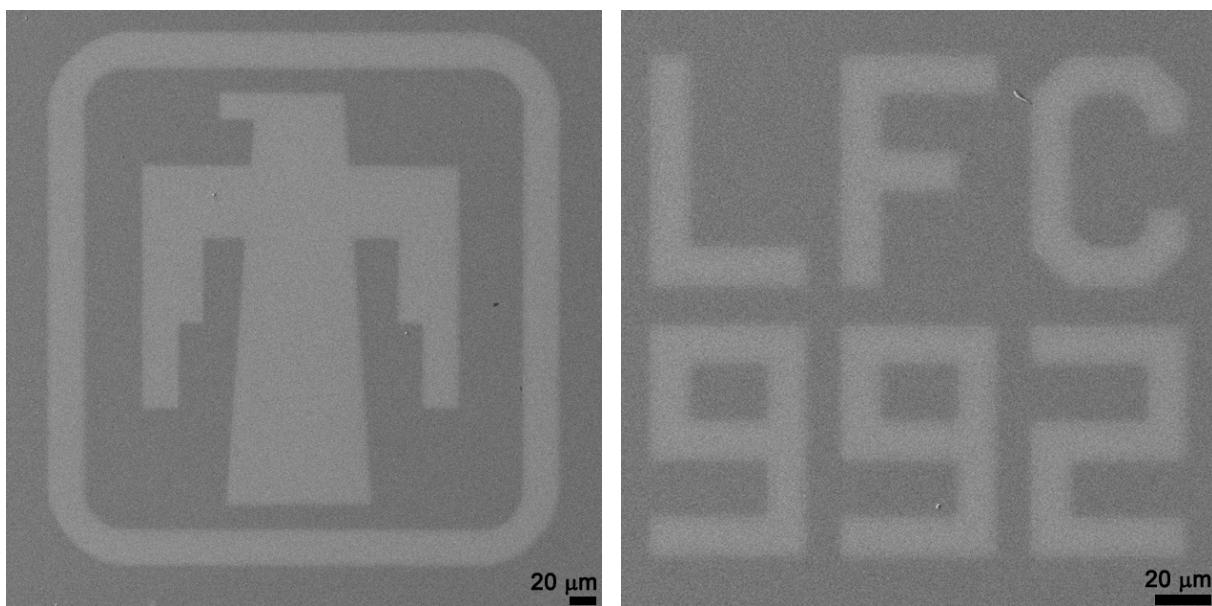
Synthesis of bis-ethylxanthate monomer. A solution of 1,4-bis(chloromethyl)benzene (8.29 g, 47.4 mmol) and *O*-ethoxyxanthic acid potassium salt (18.97 g, 118.4 mmol) were vigorously stirred in methanol (700 mL) at 40 °C for 24 h. Approximately half of the solvent was evaporated under reduced pressure (rotovap) and distilled H₂O (150 mL) was added to the mixture and stirred for 5 min. The precipitate was isolated by vacuum filtration and dried under vacuum. The desired compound was obtained without further purification as a white solid (13.22 g, 80%). mp = 115–116 °C. ¹H NMR (CDCl₃, 500 MHz): δ (ppm) 7.27 (4H, s), 4.63 (2H, q, *J* = 7.2 Hz), 4.32 (4H, s), 1.40 (6H, t, *J* = 7.2 Hz). ¹³C NMR (CDCl₃, 100 MHz): δ (ppm) 214.1, 135.3, 129.5, 70.3, 40.2, 14.0.



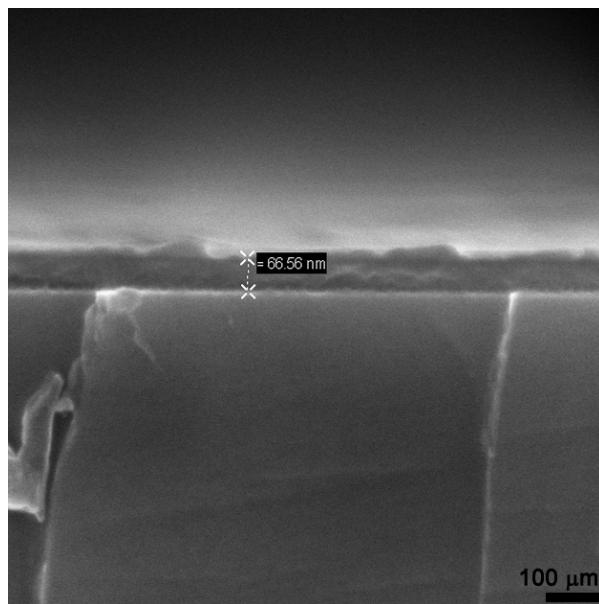
Synthesis of ethylxanthate polymer. To a stirred solution of monomer (4.85 g, 14.0 mmol) in anhydrous THF (100 mL) at 0 °C was added t-BuOK (14.0 mL, 1.0 M in THF) under a N₂ atmosphere. After 5 min of stirring, the ice bath was removed. The reaction was stirred for 1 h and poured over a stirring ice-water bath. The aqueous layer was extracted with chloroform (4 x 100 mL) and the combined organic fractions were dried over Na₂SO₄. The solvent was evaporated (rotovap) until ~100 mL remained, and the solution was poured over cold 1:1 hexanes/diethyl ether (400 mL). The mixture was transferred to centrifuge tubes and spun down. The product was isolated and dried under vacuum (1.79 g, 57%). ¹H NMR (CDCl₃, 500 MHz): δ (ppm) 7.01–6.84 (4H), 4.80 (1H), 4.51 (2H), 3.27 (1H), 3.05 (1H), 1.29 (3H). FT-IR (KBr, cm⁻¹) 2982, 1512, 1217, 1146, 1110, 1048. The number and weight average molecular weight of the precursor polymer was 51,855 and 119,633 with a polydispersity index of 2.31.

DC conductivity measurements were performed using a Keithley 6485 picoammeter with an Agilent E4980 LCR meter as the DC power supply. The polymer samples (2.5% w/w in CHCl₃) were deposited onto 5 μm spaced interdigitated electrodes (made in house). Measurements were taken under ambient conditions in the dark (to suppress photoconductivity). IV sweeps from 0–2 volts were performed and the measured current was used to calculate the specific resistance, and subsequently, the conductivity of the samples.

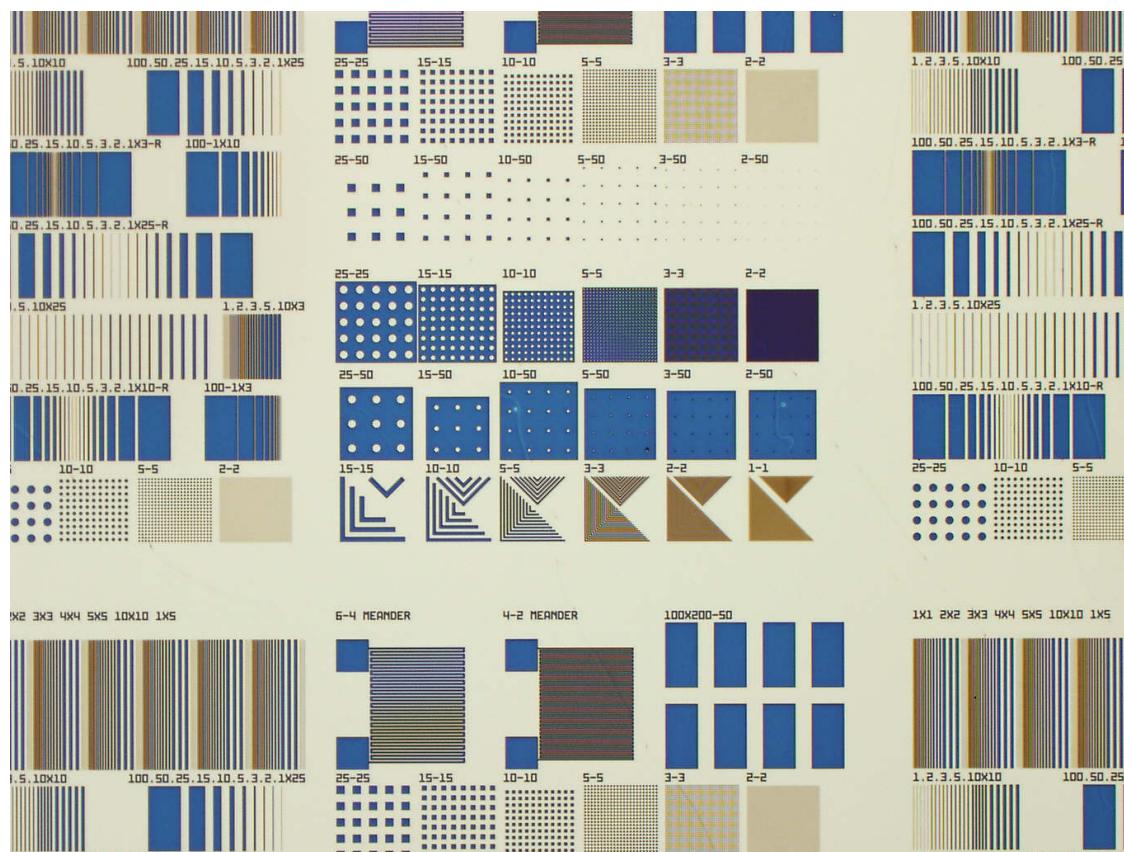
SEM images were recorded using a Zeiss Supra 55VP field emission scanning electron microscope. Samples were imaged using 5kV accelerating voltage.



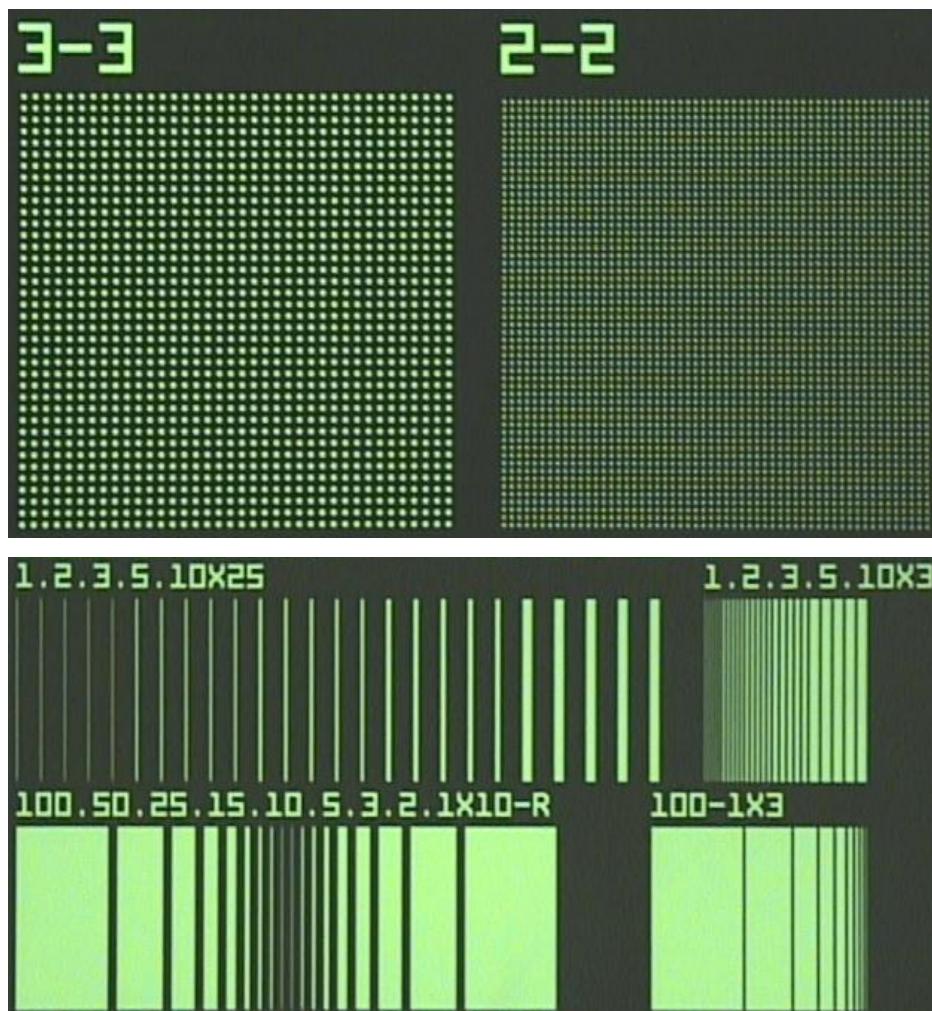
An edge-on view of the polymer film was taken by freeze-fracturing a photo-patterned polymer film on a silicon substrate. The image shows a film with a measured thickness of ~66 nm, in agreement with Dektak measurements.



Optical images were recorded either using a Clear Focus imaging system, which utilizes a Wesco DZ2 zoom microscope and a QImaging micropublisher 5.0 RTV camera or an Olympus MX80 microscope. The image below shows photopatterned PPV polymer from a Microfab qualification mask. The numbers indicate the feature size and spacing (in microns).

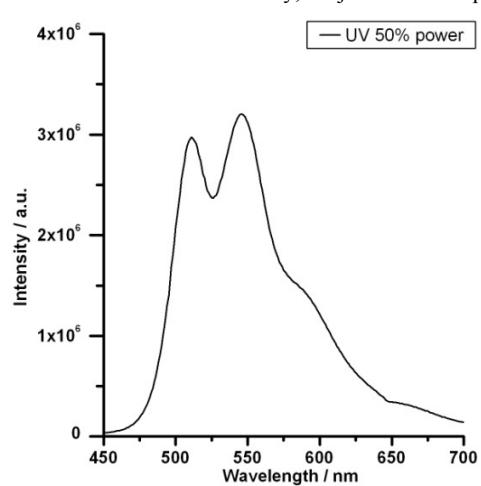


Fluorescence microscopy was performed using a Leica INM 200 microscope with a H3 filter and an excitation mode between 420 – 490 nm. The numbers indicate the feature size and spacing (in microns).



Fluorescence spectroscopy was performed using a Fluorolog FL3 spectrophotometer in “front face” mode with both the entrance and exit slits set to a 2 nm band pass and an excitation wavelength of 400 nm. A thin film sample was prepared as previously described in the UV-Vis study, subjected to 50% power from the Fusion UV system, and thermally converted (30 min at 275 °C

under a N₂ atmosphere). The spectrum recorded had a similar profile to previous literature reports.⁴



References

1. D. D. C. Bradley, *J. Phys. D.*, 1987, **20**, 1389.
2. F. Papadimitrakopoulos, K. Konstadinidis, T. M. Miller, R. Opila, E. A. Chandross and M. E. Galvin, *Chem. Mater.*, 1994, **6**, 1563.
3. E. Kesters, S. Gillissen, F. Motmans, L. Lutsen and D. Vanderzande, *Macromolecules*, 2002, **35**, 7902.
4. S. Heun, R. F. Mahrt, A. Greiner, U. Lemmer, H. Bassier, D. A. Halliday, D. D. C. Bradley, P. L. Burns and A. B. Homes, *J. Phys.: Condens. Matter*, 1993, **5**, 247.